



Call for Papers – DPS 2019

41st International Symposium on Dry Process

November 21(Thu) – 22(Fri), 2019

JMS Aster Plaza, Hiroshima, Japan



Paper Submission Deadline: July 19, 2019

Deadlines will be respected, hence early submission is encouraged.

Author instructions and information about DPS can be found at:

<http://www.dry-process.org/2019/>

The **41st** International Symposium on Dry Process (DPS2019) will be held at JMS Aster Plaza, Hiroshima in Japan, from November 21 to 22, 2019. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than three decades.

Theme: Dry processes and related technologies from fundamentals to applications

Topics:

1. Etching Technologies
2. Manufacturing Technologies (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring Systems
5. Modeling and Simulation
6. Plasma Generation (Equipment/Source)
7. Deposition Technologies (CVD / PVD)
8. Atomic Layer Processes (ALD/ALE)
9. Plasma Processes for 3D Device, FPD, Photovoltaic Devices
10. Plasma Processes for New Material Devices (MRAM, Power, Organic)
11. Plasma Processes for Biological and Medical application, MEMS
12. Atmospheric Pressure Plasma and Liquid Plasma
13. New Dry Process Concepts

Arranged session:

A1 – Novel Atomic Layer Etching and Atomic Layer Deposition approaches for advanced plasma process applications

A2 –Advanced hardware and process development for overcoming High Aspect Ratio etching (AR>100)

A3 – How AI and Deep Learning are transforming the plasma process?

For further general information, please contact: e-mail:dps2019@officepolaris.co.jp

Organizing Committee Chair: Hisataka Hayashi (Toshiba Memory Corporation)

Executive Committee Chair: Seiichiro Higashi (Hiroshima University)

Program Committee Chair: Masanori Terahara (Western Digital Corporation)

Publication Committee Chair: Tatsuru Shirafuji (Osaka City University)

URL: <http://www.dry-process.org/2019/>

DPS 2019 is co-sponsored by The Japan Society of Applied Physics

